

High Purity Ptfе Wafer Cleaning Basket Acid Resistant Silicon Wafer Carrier Fluoropolymer Etching Rack

Item Number: PL-CP284



Introduction

Ensure contamination-free semiconductor processing with our high-purity PTFE wafer cleaning baskets. Designed for aggressive etching and cleaning, these customizable carriers provide exceptional chemical resistance and thermal stability for silicon wafer handling during critical wet chemical manufacturing processes.

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Application	Description	Key Benefit
RCA Standard Clean	Sequential SC-1 and SC-2 cleaning steps to remove organic residues and metallic contaminants from silicon wafers.	Prevents metallic ion leaching, ensuring ultra-pure processing environments.
Piranha Etching	Use of sulfuric acid and hydrogen peroxide mixtures to remove heavy organic materials and photoresist.	Withstands extreme exothermic reactions and aggressive oxidation without degradation.
HF Dipping/Etching	Removal of sacrificial oxide layers or native oxides using hydrofluoric acid solutions.	Complete immunity to HF attack, which would destroy glass or quartz carriers.
Solar Cell Texturing	Immersion of silicon wafers in alkaline or acid solutions to create light-trapping surface textures.	High-volume throughput and resistance to concentrated KOH or NaOH solutions.
Post-CMP Cleaning	Removal of slurry particles and chemical residues following Chemical Mechanical Polishing.	Non-stick surface prevents slurry re-deposition on the carrier and wafers.
Photolithography	Developing and stripping steps involving aggressive organic solvents and developers.	Solvent-resistant construction ensures no swelling or softening of the carrier material.
Ultrasonic Cleaning	High-frequency acoustic cleaning of delicate electronic components in aqueous solutions.	Transmits ultrasonic energy effectively while protecting components from mechanical impact.
GaAs Processing	Wet chemical etching and cleaning of compound semiconductor substrates for optoelectronics.	Gentle, secure support for brittle substrates during critical manufacturing steps.

Parameter	Description / Specification (PL-CP284 Series)
Product Item Number	PL-CP284
Primary Material	High-Purity Virgin PTFE (Polytetrafluoroethylene)
Chemical Compatibility	Universal (Strong Acids, Bases, Solvents, Oxidizers)
Standard Wafer Sizes	Compatible with 4-inch, 6-inch, and 8-inch wafers
Customization Options	Fully customizable dimensions, slot counts, and slot widths
Handle Configurations	Fixed, removable, or robotic-compatible styles (Customizable)

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Operating Temperature	-200°C to +260°C (Continuous)	
Surface Finish	High-precision CNC machined, low-porosity surface	
Slot Design	V-shape or custom profiles for minimal contact area	
Manufacturing Process	100% CNC Machined for precision and structural integrity	
Purity Level	Trace analysis grade, metal-free manufacturing	